

FIG. 1 (PRIOR ART)

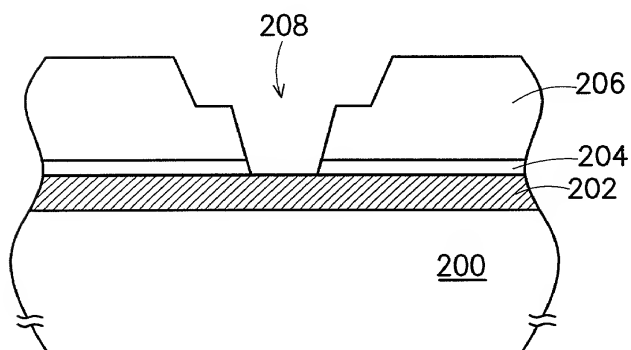


FIG. 2

Forming a dual damascene opening — 301



A post-etching cleaning step using either Fluorine-based organic solvent, or Hydrogen peroxide (H_2O_2) based organic solvent and Hydrofluoric (HF) acid solution.



Pre-cleaning step:
Sputtering argon (Ar) gas

FIG. 3